

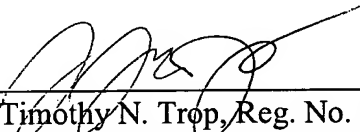
REMARKS

The clarification of the rejection is appreciated. In view of the clarification, the claims have been amended to make it clearer that a selective etchant is used. In the case of a mask, a non-selective etchant is used. Even if using a mask results in selective etching, it does not involve the use of a selective etchant. See the Semiconductor Dictionary definition attached to the previous response.

Hopefully, this overcomes the objection to form. It is noted that claim 7 was objected to although claim 7 does not include the language which was found to be objectionable. Therefore, no further amendment of that claim was undertaken.

Respectfully submitted,

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